



Abstract

The present invention proposes a manufacturing method of a display device that accomplishes a lower production cost of a display device by using means for partially forming a resist film and means for partially forming a film and etching or ashing by plasma treatment at or near the atmospheric pressure. The manufacturing method of the display device according to the invention is characterized by including a step of partially forming a conductor film at or near the atmospheric pressure and forming wirings. Here, the wirings include all kinds of wirings such as connection wirings for sending signals from external input terminals to a pixel portion, wirings for connecting thin film transistors (TFT) to pixel electrodes, and so forth, besides wirings operating as gate wirings and source wirings at the pixel portion of an active matrix type display device.